

Journal of Photochemistry and Photobiology

A: Chemistry

Volume 193 (2–3) (2008)

Asian Editor

H. Masuhara

(Kobe, Japan)

Associate Editor to Asian Editor

K. Hashimoto

(Tokyo, Japan)

European Editor

M.M. Martin

(Paris, France)

North American Editor

R. Schmehl

(New Orleans, LA, USA)

Founding Editor

R.P. Wayne

(Oxford, UK)

Editorial Board

A.U. Acuna (*Madrid, Spain*)

N.S. Allen (*Manchester, UK*)

P.F. Barbara (*Austin, TX, USA*)

F. Catalina (*Madrid, Spain*)

S.M.B. Costa (*Lisbon, Portugal*)

S. Das (*Trivandrum, India*)

J. Delaire (*Cachan, France*)

J.-P. Desvergne (*Talence, France*)

A. Douhal (*Toledo, Spain*)

H. Fukumura (*Sendai, Japan*)

K. Ghiggino (*Melbourne, Australia*)

D. Guldi (*Erlangen, Germany*)

J.L. Herek (*Amsterdam, The Netherlands*)

J. Hofkens (*Heverlee, Belgium*)

C.E. Hoyle (*Hattiesburg, MS, USA*)

D. Husain (*Cambridge, UK*)

K.C. Hwang (*Taiwan, Republic of China*)

H. Inoue (*Tokyo, Japan*)

M. Irie (*Fukuoka, Japan*)

J. Karpiuk (*Warszawa, Poland*)

H. Lemmetyinen (*Tampere, Finland*)

Y. Li (*Beijing, China*)

B. Marciniak (*Poznań, Poland*)

U. Mazzucato (*Perugia, Italy*)

T.J. Meyer (*Los Alamos, NM, USA*)

A. Mills (*Glasgow, UK*)

J.P. Mittal (*Mumbai, India*)

K. Mizuno (*Osaka, Japan*)

D.C. Neckers (*Bowling Green, OH, USA*)

E.T.J. Nibbering (*Berling-Adlershof, Germany*)

B. Ohtani (*Sapporo, Japan*)

J.C. Polanyi (*Toronto, Ont., Canada*)

V. Ramamurthy (*New Orleans, LA, USA*)

I. Saito (*Koriyama, Japan*)

M. Sauer (*Bielefeld, Germany*)

J.C. Scaiano (*Ottawa, Ont., Canada*)

R.P. Steer (*Saskatoon, Sask., Canada*)

V. Sundström (*Lund, Sweden*)

C.H. Tung (*Beijing, China*)

N.J. Turro (*New York, NY, USA*)

B. Valeur (*Paris, France*)

K.-D. Warzecha (*Mülheim, Germany*)

M. Wasielewski (*Evanston, IL, USA*)

V.W.W. Yam (*Hong Kong, PR China*)

G. Yang (*Beijing, China*)

M. Yoon (*Daejeon, Korea*)



ELSEVIER

Amsterdam • Boston • Jena • London • New York • Oxford •
Paris • Philadelphia • San Diego • St. Louis